

ABSTRACT OF THE DISCLOSURE

Antistatic compositions include a fluorochemical that is a reaction product of $R_f\text{-CH}_2\text{CH}_2\text{-SO}_3\text{H}$ with an amine wherein R_f comprises 4 or more fully fluorinated carbon atoms. These antistatic compositions can be formulated in organic solvent-based conductive coating compositions, with or without hydrophobic binders, that can be used to form conductive layers in thermally developable materials including thermographic and photothermographic materials.